

PATENT Atty. Dkt. AMAT/5975.P2/CPI/L/B/PJS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Ganguli, et al.

Serial No.: 10/811,230

Confirmation No.: 8995

Filed:

March 26, 2004

For:

Ruthenium Layer

Formation for Copper Film

Deposition

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Group Art Unit: 1762

Examiner:

Unknown

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Date

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1

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Respectfully submitted,

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Sheet 1 of 2

i	HOLLOW MINISTER AND MANAGEMENT OF THE STATE
Application Number	10/811,230
Filing Date	March 26, 2004
First Named Inventor	Ganguli, et al.
Group Art Unit	1762
Examiner Name	Unknown
Attorney Docket Number	AMAT/5975.P2/CPI/L/B/PJS
Submission Date	September 20, 2004

	U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No.1	Document Number	Publication Date	Name of Patentee or	Pages, Columns, Lines, Where Relevant Passages or Relevant	
		Number-Kind Code ^{2 (if known)}	MM-DD-YYYY	Applicant of Cited Document	Figures Appear	
	A1	US-6713373	03/30/2004	Omstead		
	A2	US-6617634	09/09/2003	Marsh, et al.		
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	A4	US-6605735	08/12/2003	Kawano, et al.		
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	A28	US-20020004293	01/10/2002	Soininen, et al.	-	

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10/811,230 Substitute for form 1449A/PTO Application Number Filing Date March 26, 2004 INFORMATION DISCLOSURE First Named Inventor Ganguli, et al. STATEMENT BY APPLICANT Group Art Unit 1762 **Examiner Name** Unknown (Use as many sheets as necessary) Attorney Docket Number AMAT/5975.P2/CPI/L/B/PJS Sheet Submission Date September 20, 2004

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Examiner Initials*	Cite No.1	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	INO.	Number-Kind Code ^{2 (# known)}			
	A29	US-20020000587	01/03/2002	Kim, et al.	
	A30	US-20010054730	12/27/2001	Kim, et al.	
	A31	US-20010006838	07/05/2001	Won, et al.	

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Examiner Initials*	Cite No.1	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ -Number ⁴ -Kind Code ⁵ (if known)				
	B1	WO 01/88972	11/22/2001		•	
	B2	JP 2001-237400	08/31/2001			
	В3	JP 2001-111000	04/20/2001			

		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No.1		
	C1	Aaltonen, et al., "Atomic Layer Deposition of Ruthenium from RuCp₂ and Oxygen: Film Growth and Reaction Mechanism Studies," Electrochemical Society Proceedings Volume 2003-08 pp. 946-953.	-
	C2	Aaltonen, et al., "Atomic Layer Deposition of Ruthenium Thin Films from Ru(thd) ₃ and Oxygen," Chem. Vap. Deposition (2004), 10, No. 4 pp. 215-219.	
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	C5	Dadgar, et al., "Growth of Ru doped semi-insulating InP by low pressure metalorganic chemical vapor deposition," Journal of Crystal Growth 195 (1998) pp. 69-73.	
	C6	Kwon, et al., "Atomic Layer Deposition of Ruthenium Thin Films for Copper Glue Layer," Journal of the Electrochemical Society, 151 (2) (2004) pp. G109-G112.	
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	C9	Lim, et al.," Atomic layer deposition of transition metals," Nature Materials, Vol. 2 November (2003) pp. 749-754.	
	C10	Shibutami, et al., "A Novel Ruthenium Precursor for MOCVD without Seed Ruthenium Layer," TOSOH Research & Technology Review, Vol. 47 (2003) pp. 61-64.	

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